

# CLAIMS

What is claimed is:

1. A method of seasoning a process chamber having interior surfaces, comprising the steps of:

cleaning said process chamber; and

providing a seasoning film on said interior surfaces of said process chamber.

2. The method of claim 1 wherein said seasoning film comprises oxide-based material.

3. The method of claim 1 wherein said seasoning film comprises silicon nitride.

4. The method of claim 1 wherein said seasoning film comprises silicon carbide.

5. A method of seasoning a chemical vapor deposition chamber having interior surfaces and a gas distribution plate, comprising the steps of:

cleaning said chamber; and

providing a seasoning film on said interior surfaces and said gas distribution plate of said chamber.

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6. The method of claim 5 wherein said seasoning film comprises silicon dioxide.

7. The method of claim 5 wherein said seasoning film comprises silicon dioxide.

8. The method of claim 5 wherein said seasoning film comprises silicon nitride.

9. The method of claim 5 wherein said seasoning film comprises silicon carbide.

10. A method of seasoning a chemical vapor deposition chamber having interior surfaces and a gas distribution plate, comprising the steps of:

cleaning said chamber; and

providing a seasoning film on said interior surfaces and said gas distribution plate of said chamber by introducing seasoning film precursor gases into said chamber.

11. The method of claim 17 wherein said seasoning film comprises silicon dioxide.

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12. The method of claim 17 wherein said seasoning film comprises silicon nitride.

13. The method of claim 17 wherein said seasoning film comprises silicon carbide.